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OPTOELECTRONICS AND COMMINICATIONS CONFERENCE 2014 AUSTRALIAN CONFERENCE ON OPTICAL FIRRE TECHNOLOGY

OECC/ACOFT 2014 - Melbourne, 6-10 July

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Model Parameter Extraction for Si Micro-Ring Modulators

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Paper Summary

Numerical values for three key model parameters that describe the transmission characteristics of Si microring modulators are extracted from measurement results. Their dependence on bias voltages is determined and their accuracy is compared with simulation results.

Introduction

Optical interconnects can offer many advantages over conventional electrical interconnects such as much higher data rates, EMI insensitivity, and smaller sizes [1]. Si photonics is a promising technology for realizing optical interconnects since Si technology provides potential for low-cost manufacturability of photonic devices and easy integration with Si electronics [2]. In particular, Si micro-ring modulators (Si MRMs) have small footprints and low driving voltages and, consequently, are actively investigated as one of the key devices for realizing Si-photonic optical interconnects [3]. Very high-speed Si MRMs with relatively low driving voltages have been demonstrated [4, 5].

In order to establish Si MRM technology based on foundry services, it is essential that accurate and convenient-to-use Si MRM models are established and the numerical values for the parameters used in those models are extracted from fabricated devices. In this paper, we demonstrate the model parameter extraction process for the Si MRM.

Structure of Si MRMs

Fig. 1. a) Structure of Si MRM b) Chip photograph of Si **MRM**

Fig. 1 shows the structure of the Si MRM and the chip photograph of the Si MRM used in our investigation. The device is fabricated by IME Si-photonics foundry service through OpSIS [6] and implemented with 0.5-µm wide, 0.22-µm thick Si waveguides on 2-µm thick buried oxide layer. The Si MRM is composed of a ring resonator surrounded by the PN junction and a

Fig. 2 Measured transmission characteristic of ring modulator $(radius = 8 \mu m, coupling gap = 0.3 \mu m, bias voltage = 0 V)$

directional coupler. The ring radius is $8 \mu m$ and the coupling gap is 0.3 um.

Light injected into the device has the wavelengthdependent transmission characteristics. Fig. 2 shows the measured transmission characteristics for the Si MRM under investigation. For the measurement, light goes into and comes out of the device through fiber probes and grating couplers. The power of injected light is minimized so that Si MRM self-heating does not occur [7]. With reverse voltages applied across the p-n junction surrounding the ring resonator, the effective group index of the ring resonator waveguide can be modulated due to the change in the depletion width resulting in shifted resonance wavelength, which modulates the intensity of the injected light.

Parameter Extraction

The Si MRM transmission characteristic can be described with the following equation [8]:

$$
T = \frac{P_t}{P_i} = \frac{\alpha^2 + \gamma^2 - 2\alpha\gamma\cos(2\pi n_{\text{eff}} L/\lambda)}{1 + (\alpha\gamma)^2 - 2\alpha\gamma\cos(2\pi n_{\text{eff}} L/\lambda)}.
$$
 (1)

In the above equation, α represents the ratio of the optical power in the ring after one round-trip to the power before the round-trip. γ represents the through coefficient for the directional coupler. With κ , the direction coupler coupling coefficient, $y^2 + \kappa^2 = 1$. n_{eff} is the effective group index of the ring waveguide. L is the circumference of the ring having the value of $50.26 \mu m$ for the device under investigation and λ is the wavelength of input light.

Our task is determining the numerical values of n_{eff} . α , and γ from measured transmission characteristics. n_{eff} can be easily determined from the resonance condition, $n_{\text{eff}}L = m\lambda_{\text{res}}$, where m is an integer. For our Si MRM, n_{eff}

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Fig. 3. RMSE dependence on α and γ

 $= 3.82659$ when the reverse bias voltage is 0V. The numerical values for α and γ can be simultaneously extracted by fitting the measured data into Eq. 1 with the minimum mean squared error (MMSE) technique. Fig. 3 shows the resulting root mean squared error (RMSE) for different values of α and γ . As can be seen in the figure, there are two pairs of α and γ , ($\alpha = 0.9688$, $\gamma = 0.973$) and ($\alpha = 0.973$, $\gamma = 0.9688$) that produce the minimum RMSE. This is because interchanging α and γ in Eq. 1 produces the same result. The correct pair should be determined by performing additional measurement.

In MRMs, the transmitted power at the resonance wavelength becomes zero for critical coupling, which occurs when depletion width increases and the light guided in the ring waveguide experiences less carriers, which increases *α*. However, γ does not change with the reverse bias since the directional coupler does not have any PN junction around it. Consequently, if $\alpha < \gamma$ for a given MRM, applying a reverse bias will produce less transmitted power at the resonance wavelength as it approaches critical coupling with increased α , but if $\alpha > \gamma$, the transmitted power at the resonance will be larger with a reverse bias [8]. The circles in Fig. 4 show measured transmission characteristics at three different biases. As can be seen, the transmitted power at the resonance decreases with the reverse bias indicating $\alpha < \gamma$ for our Si MRM. From this, we can choose the correct pair of $(a =$ 0.9688, $\gamma = 0.973$) for the Si MRM with 0V bias. The n $\alpha = \gamma$. With the reverse bias applied, the

Fig. 4. Measured and fitted transmission characteristics

Table 1. Extracted α and γ values

Fig. 5. Extracted γ from measurement and simulation

red line in Fig. 4 shows the calculated result from Eq. 1 with extracted parameter values. Similar process can be applied for the cases of -1 and -2 V biases and the results are shown in Fig. 4 and Table 1.

Comparison with Simulation

In order to check the accuracy of the extracted values, we experimentally extract *γ* values from five different Si MRMs having different couple gap values ranging from 0.26 μm to 0.34 μm and compare them with *γ* values determined from numerical simulation. For the simulation, Lumerical MODE Solution is used for the directional waveguides having the identical structure as in measured Si MRMs. Fig. 5 shows extracted and simulated *γ* values for different gap values. They agree well within about 0.2%. The slight difference is believed due to the fact that the fabricated waveguides do not have vertical sidewalls [9], which cause more coupling than vertical-sidewall waveguides used in simulation, resulting in less *γ* values. bee
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Conclus sions

We demonstrated the values for the key model parameters can be extracted from measured Si MRM tran nsmission ch aracteristics. We also c ompared the extracted values with simulation results.

Referen nces

- 1. M. Lipson et al., Journal of Lightwave Technology Vol 23 No.12 (2005) 4222-4238
- 2. R. Ding, et al., OFC/NFOEC Technical Digest (2012) OM2E.6
- 3. A. Ayazi *et al*., Optics Ex xpress Vol. 20 No. 12 (2012) 13115-13122 2
- 4. G. Li et al., Optics Express Vol. 19 No. 21 (2011) 20435-20443
- 5. T. Baba *et a al*., Optics Exp press Vol. 21 No. 10 (2013) 11869-11876 6
- 6. M. Hochberg et al., IEEE Solid-State Circuits Magazine (2013) 48-58 8
- 7. X. Zheng *et al*., Optics Ex xpress Vol. 20 No. 10 (2012) 11478-11486 6
- 8. W. Bogaerts et al., LASER&PHOTONICS REVIEWS Rev. 6 No. 1 (2012) 47–73
- 9. T. Baehr-Jones et al., OpSIS Design rule manual Version 2.61 (2013)